

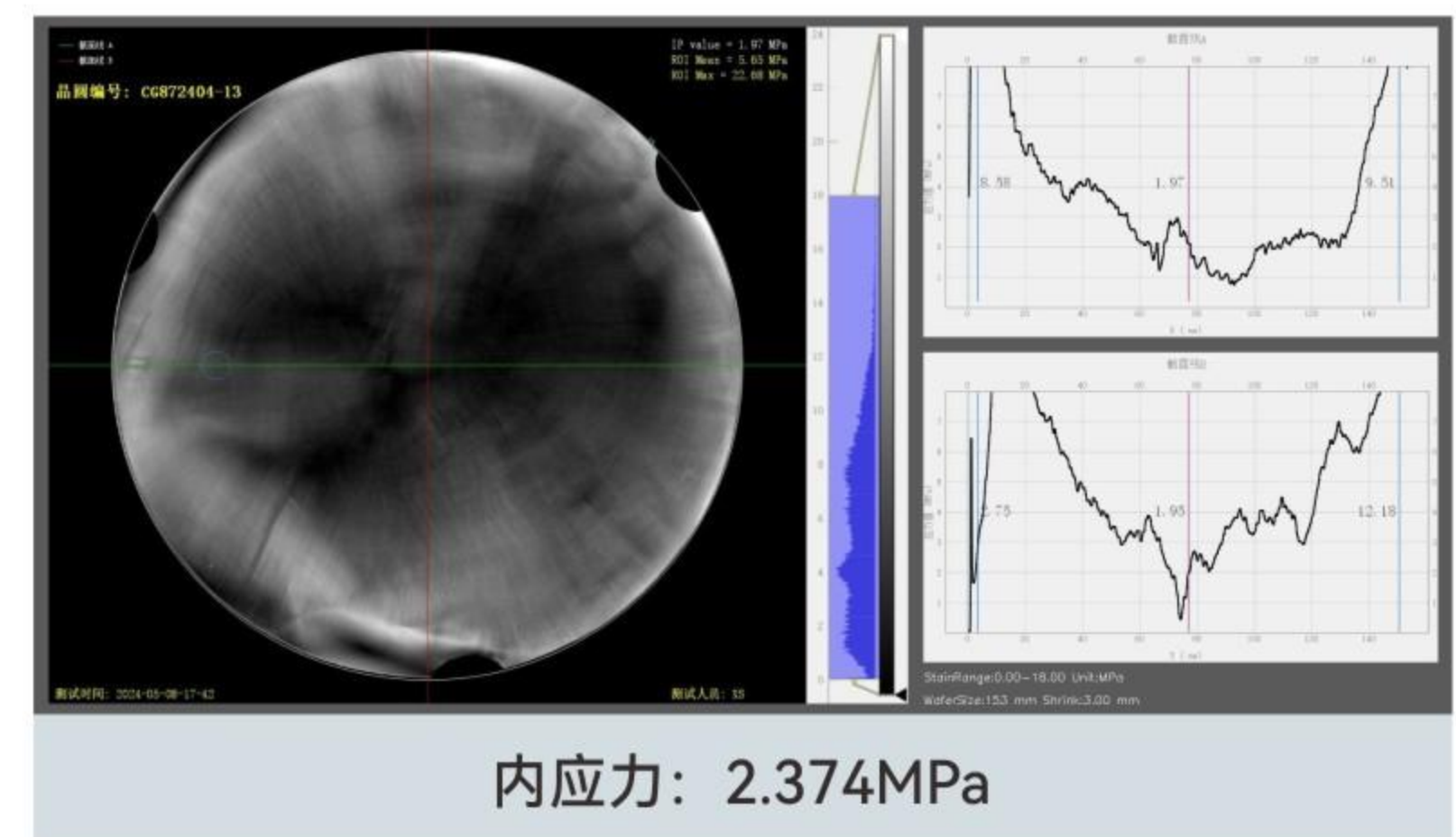
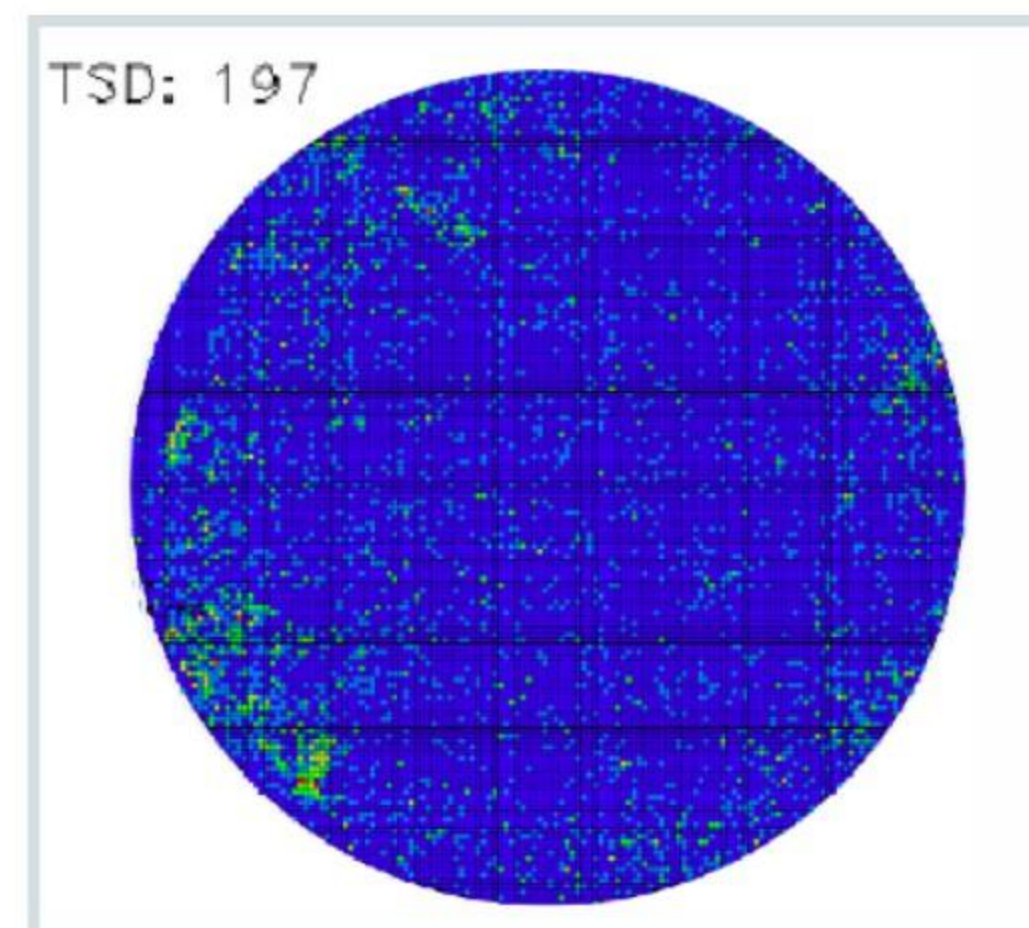
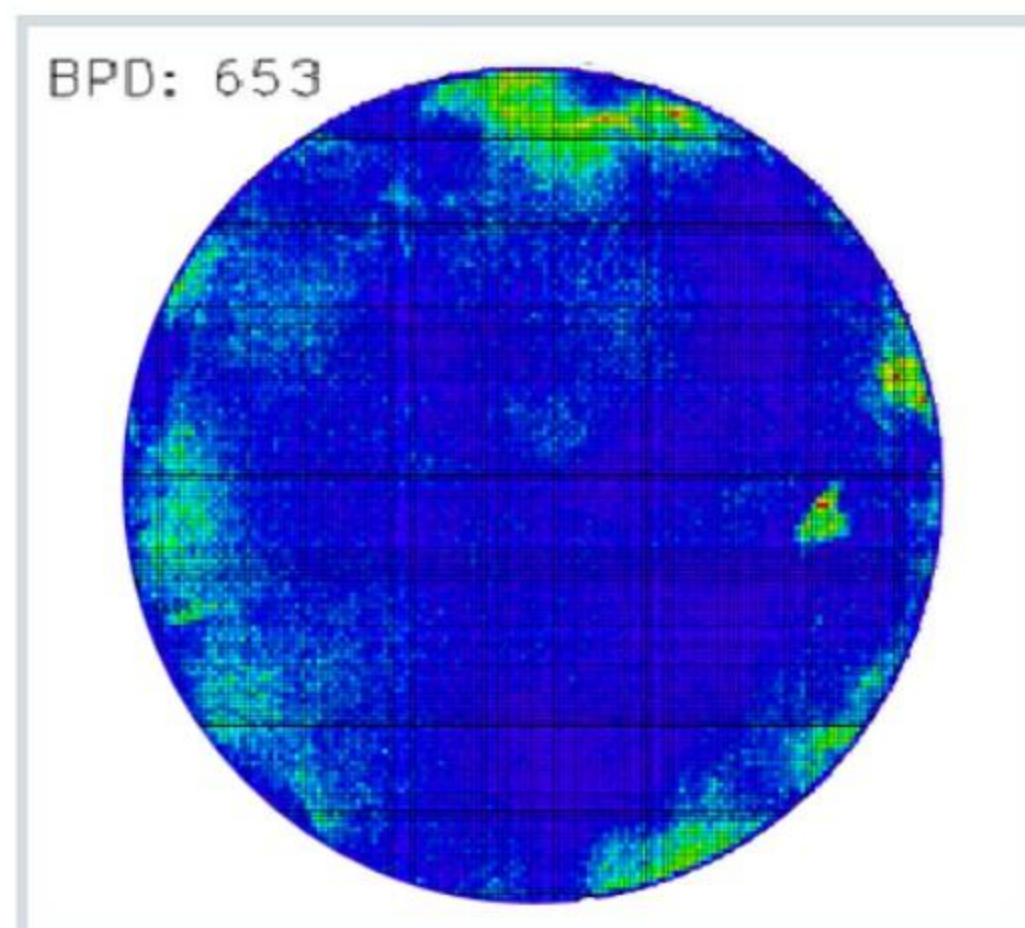


8英寸SiC导电型 衬底单晶片

产品特点 FEATURE

- ✓ 位错密度低
- ✓ 电阻率可控
- ✓ 面型平整度好
- ✓ 性能一致性好

位错密度: BPD: 653 ea/cm²; TSD: 197 ea/cm²



产品选型 SELECTION

| 项目 | 单位 | 8-inch | |
|--------|------|------------------------|-----------|
| | | P级 | R级 |
| 晶片取向 | ° | 4.0 toward <11-20>±0.5 | |
| 4H晶型面积 | / | 100% | ≥90% |
| 直径 | mm | 200.2±0.2 | |
| 厚度 | μm | 500±25 | |
| 平整度 | TTV | μm | ≤15 |
| | BOW | μm | -30~30 |
| | Warp | μm | ≤40 |
| Si面粗糙度 | nm | ≤0.5 (AFM 10*10μm) | |
| 电阻率 | Ω·cm | 0.015~0.025 | 0.01~0.03 |
| 缺陷密度 | 微管密度 | ea·cm ⁻² | ≤0.5 |
| | BPD | ea·cm ⁻² | ≤5000 |
| | TSD | ea·cm ⁻² | ≤550 |
| | TED | ea·cm ⁻² | ≤7500 |

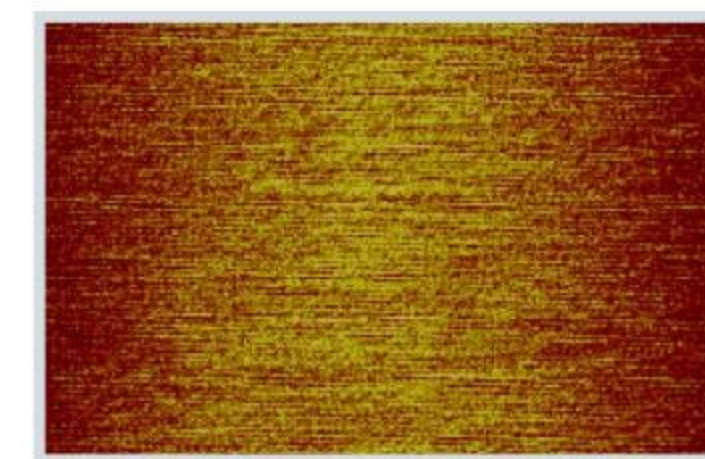
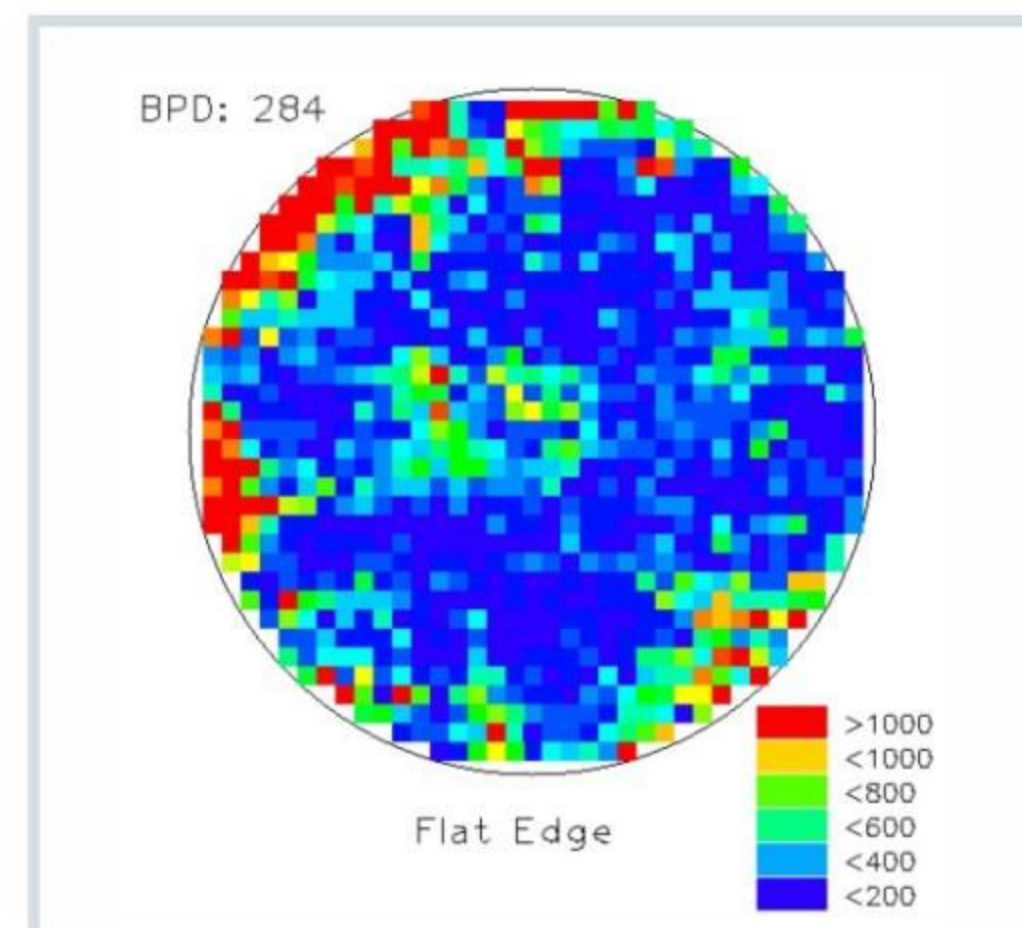
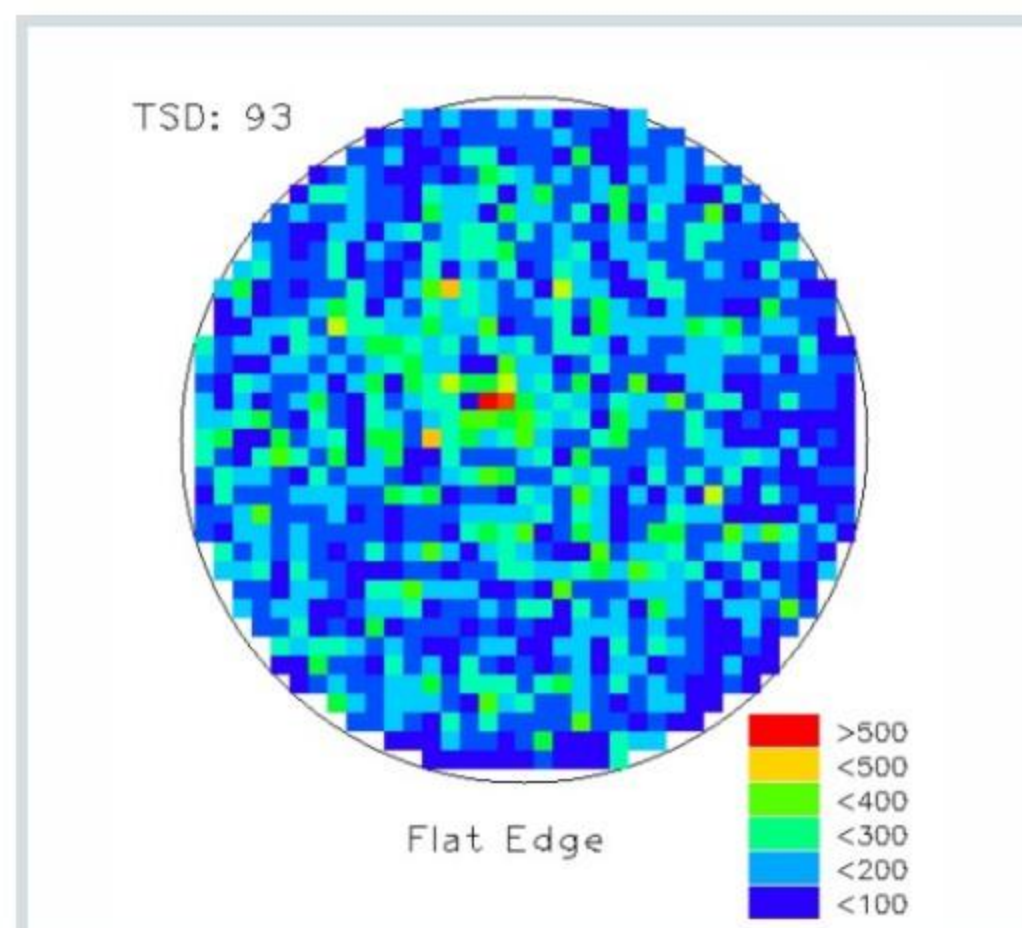


6英寸SiC导电型 衬底单晶片

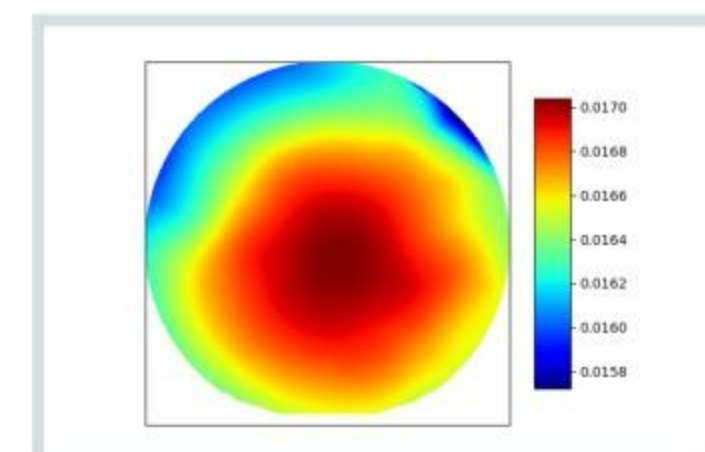
产品特点 FEATURE

- ✓ 禁带宽度大
- ✓ 高击穿电场
- ✓ 抗辐射化学稳定性好
- ✓ 高热导率
- ✓ 本征温度高
- ✓ 电子饱和漂移速度高

位错密度: BPD: 284 ea/cm²; TSD: 93 ea/cm²



Si极性面表面粗糙度
Ra=0.0678nm



电阻率
0.01554-0.01703Ω·cm

产品选型 SELECTION

| 项目 | 单位 | 6-inch | | | |
|--------|------|--|--------|-------------|--------|
| | | P-MOS级 | P-SBD级 | D级 | |
| 晶片取向 | ° | 4.0 toward $\langle 11-20 \rangle \pm 0.25$ | | | |
| 4H晶型面积 | / | 100% | | | |
| 直径 | mm | 150±0.2 | | | |
| 厚度 | μm | 350±20 | 350±25 | | |
| 平整度 | TTV | μm | ≤5 | ≤10 | ≤15 |
| | BOW | μm | -10~10 | -20~20 | -25~25 |
| | Warp | μm | ≤25 | ≤30 | ≤35 |
| Si面粗糙度 | nm | ≤0.2 (AFM 10*10μm) | | | |
| 电阻率 | Ω·cm | 0.015~0.025 | | 0.015~0.028 | |
| 缺陷密度 | 微管密度 | ea·cm ⁻² | ≤0.1 | ≤0.5 | |
| | BPD | ea·cm ⁻² | ≤800 | ≤3000 | ≤9000 |
| | TSD | ea·cm ⁻² | ≤200 | ≤500 | ≤1000 |
| | TED | ea·cm ⁻² | ≤3000 | ≤3000 | ≤7000 |

